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ABSTRACT

An apparatus and method for preventing damage to a chamber wall by a baffle plate in a semiconductor fabrication system during a semiconductor fabrication operation is disclosed herein. An electrostatic chuck is associated with the semiconductor fabrication system. A gauge for measuring a gap between said baffle plate and the chamber wall can be utilized to prevent damage to the chamber wall by the baffle plate during a movement of the electrostatic chuck during the semiconductor fabrication operation. Such a semiconductor fabrication operation can comprise, for example, a wet cleaning semiconductor operation.

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